

## <sup>11</sup>Boron Trifluoride Electronic Grade.



<sup>11</sup>BF<sub>3</sub> has applications in silicon semiconductor manufacturing as a P-type dopant. It is used where shallow, high concentration boron doping is needed. It can be applied via ion implantation or chemical vapor deposition (CVD). <sup>11</sup>BF<sub>3</sub> is a colorless, toxic, non-flammable, corrosive high pressure gas.

Specification	Analytical Value	Test Method
<sup>11</sup> B Enrichment	99.8 atom%	MS
Boron Trifluoride	99.99%	GC
Nitrogen	< 15 ppm	GC
Oxygen + Argon	< 30 ppm	GC
Carbon Dioxide	< 15 ppm	GC
Sulfur Dioxide	< 10 ppm	FTIR
Silicon Tetrafluoride	< 10 ppm	FTIR

\*A large variety of cylinder sizes and valve options are available. Please inquire about specific packaging needs.\*

### Linde Electronics and Specialty Gases

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